



Attorney Docket No. 253/006 CIP 2

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re the Application of:

Jung-ho LEE, et al.

Art Unit: 2818

Serial No. 10/779,733

Examiner: Renee R. Berry

Filed: February 18, 2004

*Confirmation No. 2084*

For: **METHOD OF FORMING SILICON OXIDE LAYER  
IN SEMICONDUCTOR MANUFACTURING  
PROCESS**

**AMENDMENT UNDER 37 C.F.R. §1.312**

Mail Stop Issue Fee  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, Va. 22313-1450

Sir:

**INTRODUCTORY COMMENTS**

In connection with the payment of the issue fee filed concurrently herewith,  
applicants respectfully submit the following amendments and remarks:

**Amendments to the Drawings** begin on page 2 of this paper.

**Remarks** begin on page 3 of this paper.